



Hydrogen Isotope Interaction with Boron Layers

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Motivation

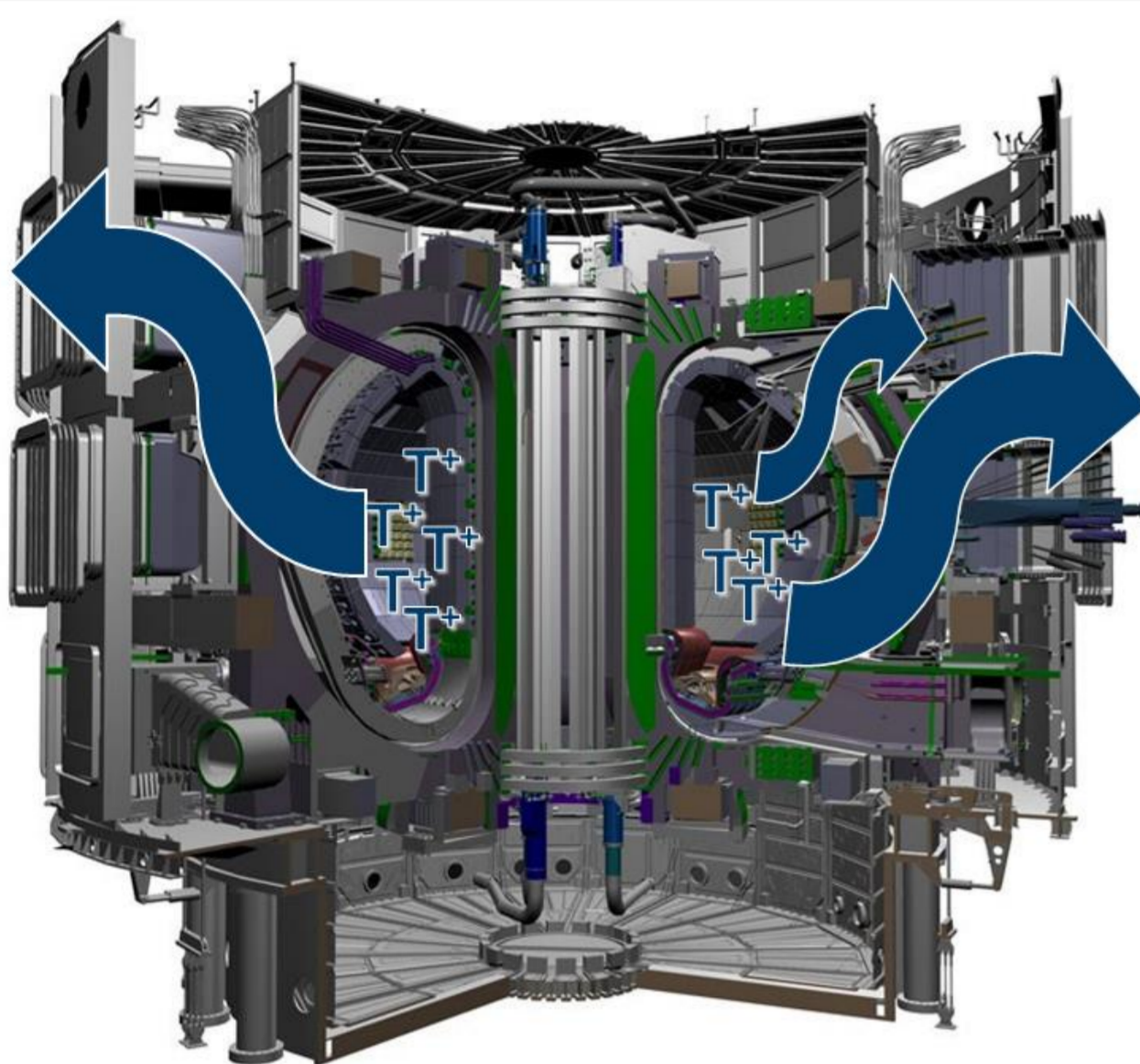


Figure (edited): <http://www.iter.org/>

Hydrogen isotope permeation and retention in fusion devices:

- Fuel loss and unpredictable fueling
- Tritium accumulation

The study of hydrogen interaction with fusion materials is necessary!

Due to the ITER re-baseline:
Fabrication and investigation of thin boron coatings.

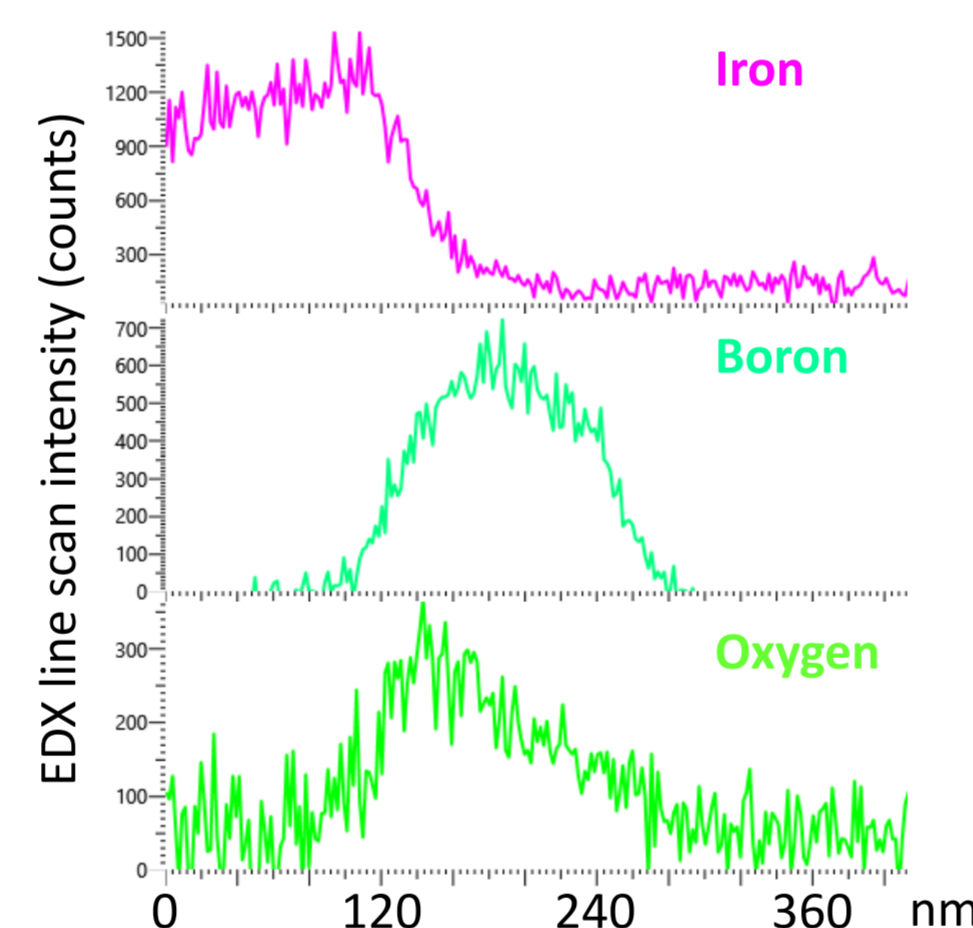
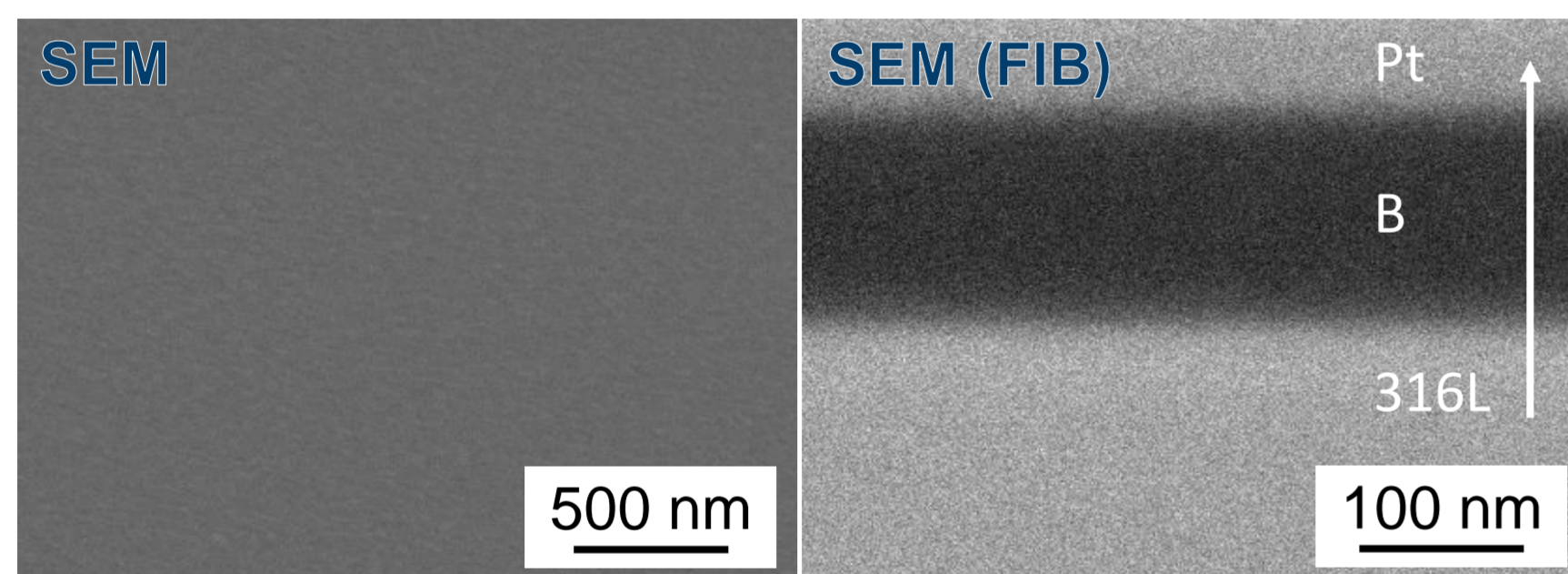
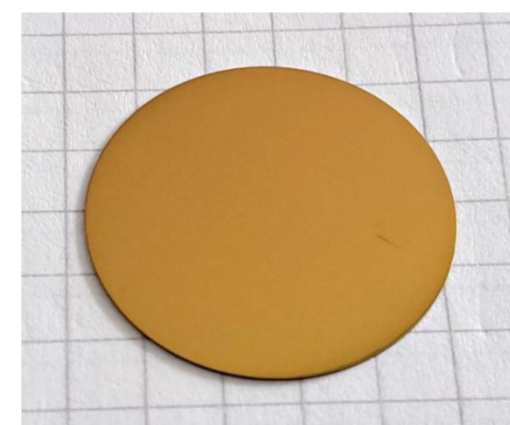
Samples

Sample preparation:

- Magnetron sputter deposition: RF-mode with pure boron target and Ar plasma
- Coated on both sides with same deposition parameter (5.5 h deposition)
- Substrates: polished 316L-ITER Grade, 24 mm in diameter, 0.3 mm thickness (and polished W (Plansee))
- Annealing at 550°C in vacuum → stable, no peeling, no change of layer

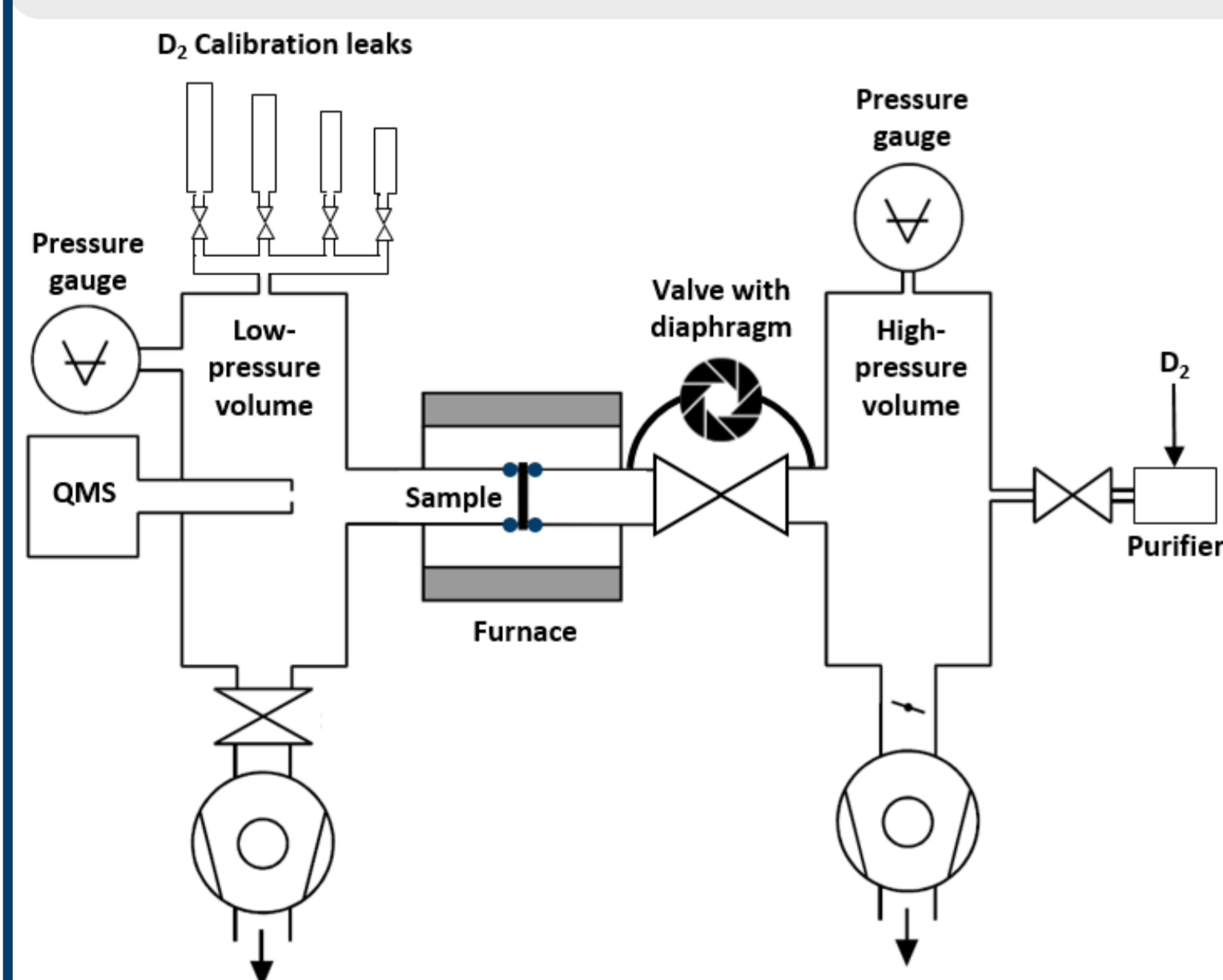
Sample characterization:

- SEM: smooth, dense layer
- SEM(FIB): - layer thickness: 110 nm per side
- homogeneous layer
- EDX: oxygen on interface to steel, less in B layer
- XRD: amorphous



→ B layer on W: see [Excuse – Boron Layers](#)

Permeation Measurement

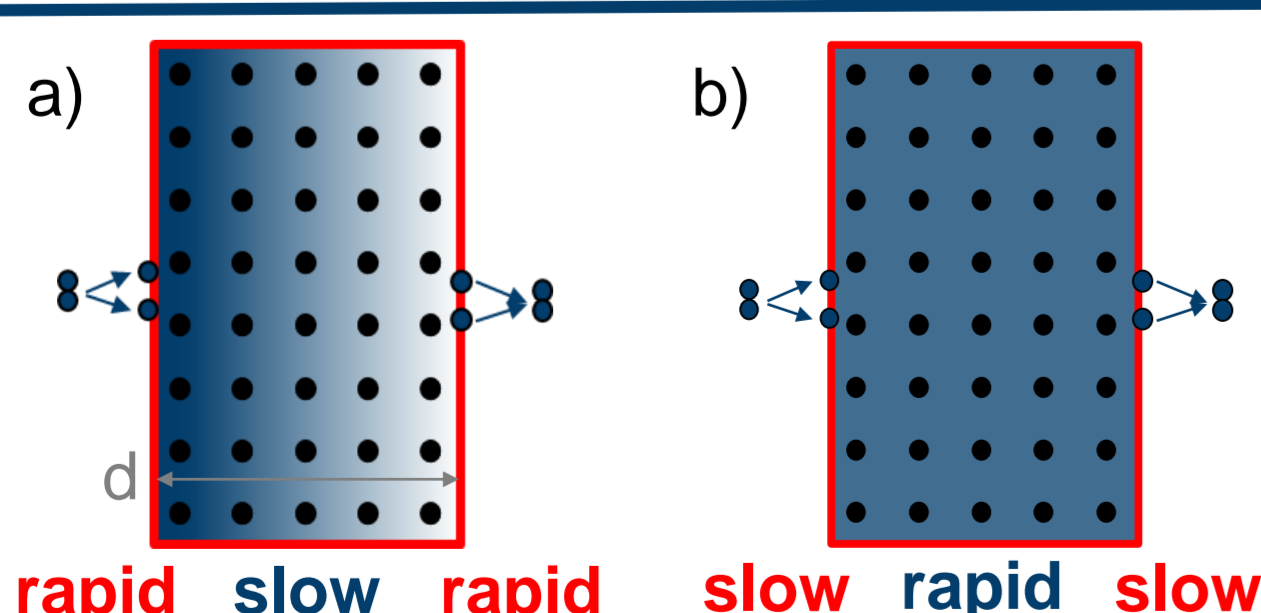


Device specifications:

- D₂ purifier → no oxidation of sample during measurement
- Installation of a valve with baffle → rapid D₂ inlet → 'Lag-time' → determination of diffusion (D)

Measurement procedure:

- Evacuation (10⁻⁹ mbar), calibration
- Temperature (T) range: 300 - 550°C, up/down (sample stability)
- Pressure (p) range: 25-800 mbar
- Lag-time measurement



Pressure dependence (p): 25-800 mbar: permeation control mechanism (J_p = permeation flux):

- a) J_p ∝ √p: diffusion limited, dependent on sample thickness (d)
- b) J_p ∝ p: surface limited, independent on d

Layer permeability:

- Substrate and layer thickness independent
- Valid in diffusion limited regime

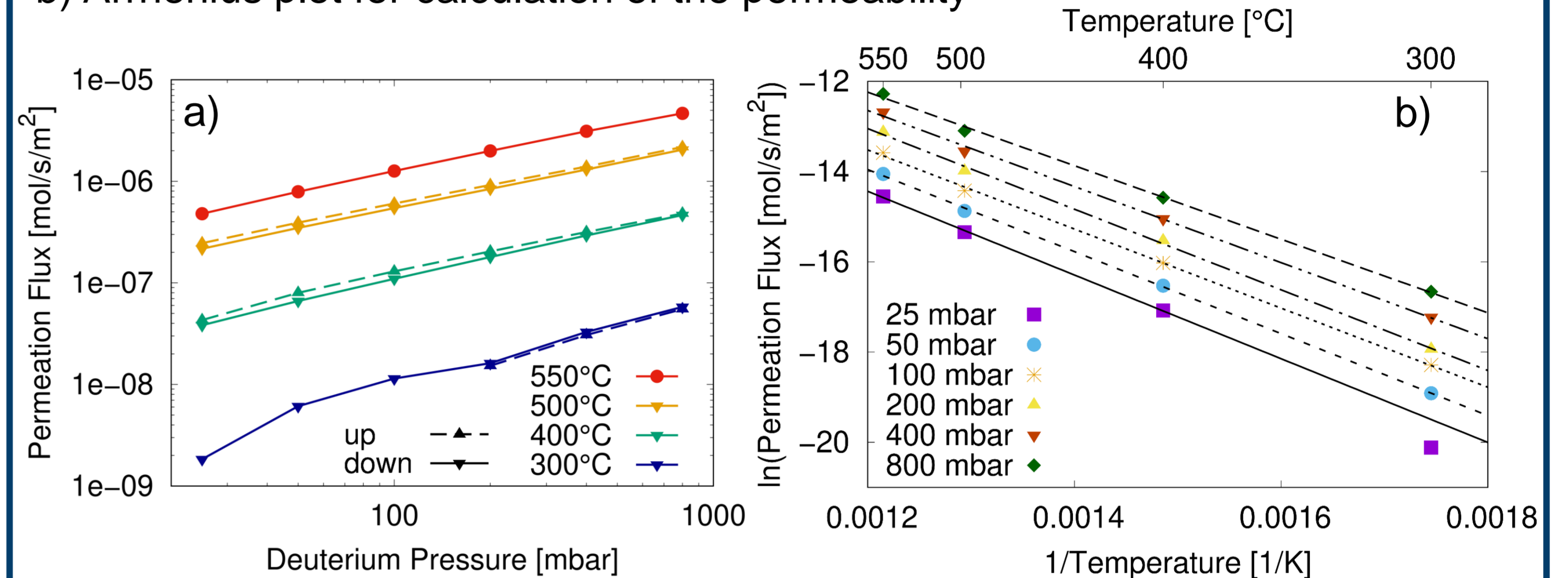
$$P_{lay} = \frac{d_{lay}}{\left(\frac{d_{tot}}{P_{tot}} - \frac{d_{sub}}{P_{sub}}\right)}$$

lay: layer
tot: total
sub: substrate

Results

Permeation flux (J_p) measurement through the coated sample:

- a) Permeation flux vs. applied deuterium pressure for all temperatures
- b) Arrhenius plot for calculation of the permeability

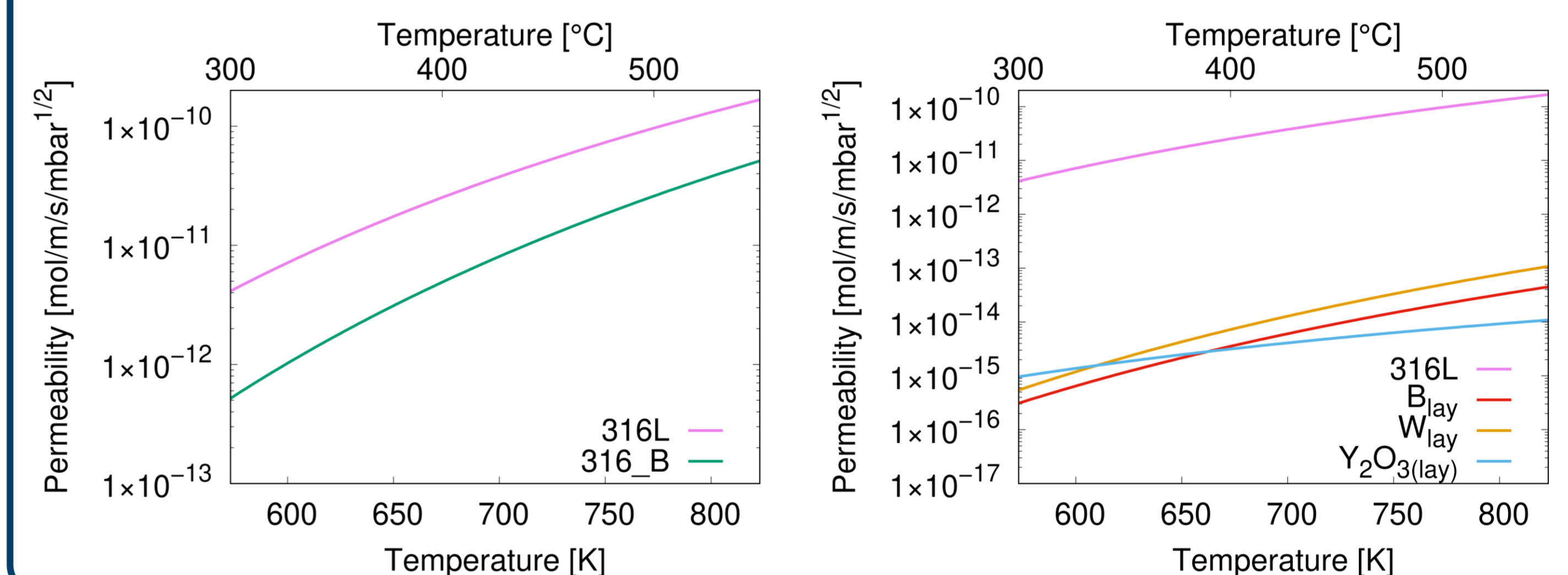


Comparison up/down measurement: No change of sample

Pressure dependence: J_p ∝ p^{-0.65}: Diffusion limited to intermediate regime

p/T-dependent measurement: J_p = $\frac{P_0 \sqrt{p}}{d} e^{-\frac{E_p}{RT}}$ → permeability + layer permeability

Sample	P _{0(tot)} [$\frac{\text{mol}}{\text{ms}\sqrt{\text{mbar}}}$]	E _{p(tot)} [$\frac{\text{kJ}}{\text{mol}}$]	P _{0(layer)} [$\frac{\text{mol}}{\text{ms}\sqrt{\text{mbar}}}$]	E _{p(layer)} [$\frac{\text{kJ}}{\text{mol}}$]
316L	8(1) · 10 ⁻⁷	58(1)	-	-
316L_B	1.9(5) · 10 ⁻⁶	72(2)	4 · 10 ⁻⁹	78



Conclusion and Outlook

Conclusion:

- The permeation flux is reduced by about one orders of magnitude due to thin (~220 μm) B coating compared to a non-coated 316L substrate
- B_{lay} permeability around four orders of magnitude lower as permeability of 316L substrate
- B_{lay} permeability in the same order of magnitude as W_{lay} and the permeation barrier Y₂O_{3(lay)} permeability
- **Low hydrogen permeability of pure, amorphous B layers**

Outlook:

- Ongoing study of permeability of one side B coated 316L substrate
- Investigation of permeability of mixed B layers, e.g. with W, O, D
- Deuterium retention measurements on D₂ filled B layers on W and 316L substrates
- D₂ filling of B coated samples by gas, plasma and ions
- Investigation of sputter rate from D plasma and ions on B coating

Excuse – Boron Layers

Magnetron sputter deposition of pure boron layers on W substrates:

- Polished and annealed W samples: 1 x 1 cm² and PSI-2 geometry
- Same deposition parameter and B layer characteristics as on steel substrates
- BUT: after some time (~weeks) development of purple dots/blister: W oxide?
- study ongoing (EDX, XPS), keep under vacuum after polishing / annealing
- Annealing up to 1000°C → no change of sample state

B layer on W:

